PROCEEDINGS OF SPIE

Optical Micro- and Nanometrology VI

Christophe Gorecki
Anand Krishna Asundi
Wolfgang Osten
Editors

5–7 April 2016
Brussels, Belgium

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Published by
SPIE

Volume 9890

Proceedings of SPIE 0277-786X, V. 9890

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Optical Micro- and Nanometrology VI, edited by Christophe Gorecki, Anand Krishna Asundi, Wolfgang Osten,
Proc. of SPIE Vol. 9890, 989001 · © 2016 SPIE · CCC code: 0277-786X/16/$18 · doi: 10.1117/12.2243899

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Please use the following format to cite material from these proceedings:
Author(s), "Title of Paper," in *Optical Micro- and Nanometrology VI*, edited by Christophe Gorecki, Anand Krishna Asundi, Wolfgang Osten, Proceedings of SPIE Vol. 9890 (SPIE, Bellingham, WA, 2016) Six-digit Article CID Number.

ISSN: 0277-786X
ISSN: 1996-756X (electronic)
ISBN: 9781510601352

Published by
SPIE
P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445
SPIE.org

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